NMP (1-Methyl-2-pyrrolidinone) ALEG®

Positive Photoresist Stripper





Material No.: 6397-05 Batch No.: 0000165675 Manufactured Date: 2017/01/01

Retest Date: 2021/12/31

Certificate of Analysis

Test	Specification	Result
Assay (C5H9NO)	>= 99.5 %	99.7
Color (APHA)	<= 20	<5
Water (H2O)(by Karl Fischer titrn)	<= 0.05 %	0.02
Free Amines (as CH3NH2)	<= 50 ppm	< 1
Chloride (Cl)	<= 0.5 ppm	0.1
Phosphate (PO4)	<= 1 ppm	< 1
Trace Impurities – Aluminum (Al)	<= 100.0 ppb	0.8
Arsenic and Antimony (as As)	<= 100 ppb	< 100
Trace Impurities – Barium (Ba)	<= 100.0 ppb	< 0.5
Trace Impurities – Boron (B)	<= 100.0 ppb	2.0
Trace Impurities – Calcium (Ca)	<= 300.0 ppb	4.0
Trace Impurities – Chromium (Cr)	<= 100.0 ppb	< 1.0
Trace Impurities – Cobalt (Co)	<= 100.0 ppb	< 1.0
Trace Impurities – Copper (Cu)	<= 100.0 ppb	< 0.5
Trace Impurities – Gold (Au)	<= 100.0 ppb	0.7
Trace Impurities – Iron (Fe)	<= 100.0 ppb	16.0
Trace Impurities – Lead (Pb)	<= 100.0 ppb	< 3.0
Trace Impurities – Lithium (Li)	<= 100.0 ppb	< 0.5
Trace Impurities – Magnesium (Mg)	<= 100.0 ppb	< 0.5
Trace Impurities – Manganese (Mn)	<= 100.0 ppb	< 1.0
Trace Impurities – Nickel (Ni)	<= 100.0 ppb	< 1.0
Trace Impurities – Potassium (K)	<= 100.0 ppb	< 4.0
Trace Impurities – Silver (Ag)	<= 100.0 ppb	< 1.0
Trace Impurities - Sodium (Na)	<= 300.0 ppb	5.0

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<= 100.0 ppb <= 100.0 ppb	< 0.5 < 2.0
<= 100.0 ppb	< 2.0
	1 = 10
<= 100.0 ppb	< 1.0
<= 100.0 ppb	< 0.5
<= 100.0 ppb	1.0
<= 10 par/ml	2
<	<= 100.0 ppb <= 100.0 ppb

For Microelectronic Use

Country of Origin: US

Packaging Site: Phillipsburg Mfg Ctr & DC



Phillipsburg, NJ 9001:2008, 14001:2004, FSSC 22000
Paris, KY 9001:2008
Mexico City, Mexico 9001:2008
Deventer, The Netherlands 9001:2008, 14001:2004, 13485:2003
Gliwice, Poland 9001:2008, 13485:2012
Selangor, Malaysia 9001:2008
Dehradun, India, 9001:2008, 14001:2004, 13485:2003
Mumbai, India, 9001:2008
Panoli, India 9001:2008

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